Search Query DBs 451/56:ccls: US-PCPUB: USPAT:	.80
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451/60.ccls. US-PGPUB. US-	ی کے کے
polish\$3 US-PGPUB. USPAT: EPO; JPO; DERWENT	
451/41.ccls. and polish\$3 US-PGPUB, USPAT; USPAT; EPO; JPO; DERWENT	
451/56.ccls. and polish\$3 US-PGPUB. USPAT: EPO; JPO; DERWENT	
451/60.ccls. and polish\$3 US-PGPUB. USPAT; EPO; JPO; DERWENT	
pad US-PGPUB. USPAT; EPO; JPO; EPO; JPO;	
"3-hydroxy-4-pyrones" US-PGPUB; USPAT; EPO; JPO; DERWENT	
('3-hydroxy-4-pyroness') or US-PGPUB. ('hydroxy adjl butyrolactones) or USFAT. broane bronzhednes (dalkylamine EPO, JPO, adj broanes) formaldehyde (formic BEWENT adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trhydroxyheraene (solvated adj electrons) (sulfurous adj acid)	

2004/09/22 13:17	2004/09/22 13:18	2004/09/72 13:18	2004/09/22 13:18	2004/09/22 13:18	2004/09/22 13:19	2004/09/22 13:23
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OR	ő	%	QR	S.	OR	98
US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO, JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB: USPAT: EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO: JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT
("3-hydroxy-4-pyrones") or (hydroxy adj1 butyrolactones) or borane or borbhydrides or (dialkylamine or formic adj acid) or hydrogen or hydroguinones or hydrogen or hydroguinones or hydroxybnous adj acid) or trihydroxybnous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)	("428" or "156" or "51"), das.	(("3-hydroxy-4-pyrones") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (suffurous adj acid)) and (("428" or "156" or '51"),cdas.)		"451".clas.	((73-hydroxy-4-pyrones*) or (hydroxy-adji butyrobactones) or borane borohydrdes (dalkyamine adj boranes) formaldehyde (formto adj acdj hydrogen hydroquinones hydroxyamine (hypophosphorous adj acdj thiydroxybenzene (solvated adj electronis) (suffurous adj acdj) and "451", dass	reducing agent
955901	303143	43264	0	64433	2601	2868440
510	S11		S13	514	SIS	516

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2004/09/22 13:23	2004/09/22 13:34	2004/09/22 13:31	2004/09/22 13:31	2004/09/22 13:42
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&	OR	OR	OR	o _R
US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT, EPO; JPO, DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT
((("3-thydroxy-4-pyrones") or (hydroxy adj 1 butyrolactones) or borane boronydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxyloenzene (solvatet ad aelectrons) (suffurous adj acid) 1 and "451".das.) and (reducing agent)	(451/41:cds, and polisits)) and pad	(451/56.ccls. and polish\$3) and pad	(451/60.ccts, and polish\$3) and pod	(("3-hydroxy-4-pyrones") or (hydroxy adj 1 butyrolactones) or borane boronbydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphosphorous adj acid) trihydroxybenzene (solvated adj electrone) (sulfurous adj acid) trihydroxybenzene (solvated adj electrone) (sulfurous adj acid)) and (((451/41.ccls. and polish\$3) and pad) or ((451/60.ccls. and polish\$3) and pad) or ((451/60.ccls. and polish\$3) and pad) or ((451/60.ccls. and polish\$3) and pad))
833	1562	396	263	337
517	518	519	520	221

2004/09/22 13:35	2005/01/24:13:20	2004/09/22 13:38
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80	Š.	OR
US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB. USPAT. EPO: JPO: DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT
((('3-hydroxy-4-pyrones') or (hydroxy adj1 butyrolactones) or borane bronzh brotharbetanie adj boranes) formaldehyde (formic adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrone) (sulfurous adj acid) 1 and (((451/41.cds. and polish\$3) and pad) or ((451/56. cds. and polish\$3) and pad) or ((451/60.cds. and polish\$3) and pad) and ((('3-hydroxy-4-pyrones') or (hydroxy adj1 butyrolactones) or horane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid)) and (((451/41.cds. and polish\$3) and pad) or ((451/56. cds. and polish\$3) and pad) or ((451/56. cds. and polish\$3) and pad) or ((451/56. cds. and polish\$3) and pad))))	88 ((451/41.ccks. and polish\$3) and US-PGPUB. OR pad) and US-PGPUB. OB pad) and US-PGPUB. OB pad) and US-PGPUB. OB pad) and US-PGPUB. OBENWENT Provided by the pad of parameter process of page parameter process of page page page page page page page page	(("3-hydroxy-4-pyrones") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphrous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and (((451/56 ccfs. and polish\$3) and pad) or ((451/66. ccfs. and polish\$3) and pad))
64	288	83
225	S	

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Search History 1/24/05 4:22:37 PM Page 3 C:\APPS\EAST\Workspaces\10753138.wsp

2004/09/72 13:39	2004/09/72 14:22	2004/09/22 14:18	2004/09/72.14:19	2004/09/22 14:22	2004/09/72 14:23	2004/09/22 14:23	2005/01/21 15:29	2005/01/21 15:11	2005/01/21 15:12
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US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	USPAT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT
((73-hydroxy-4-pyrones*) or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybertzene (solvate adj electrons) (sulfurous adj acid) and ((451/41.ccis. and polist\$3) and pad)	oxidize\$4 and abrasive and polish\$4	oxidize\$2 and abrasive and polish\$4 and (reducing adj agent) and ((liquid or aqueous) adj carrier)	("4769046" "5489233" "5527423" "5958794" "6001289" "6011200" "6117783" "6126332" "529070004360" "2002/0012322" "2002/0012322"	tantalum	451/41 ccls	tantalum and 451/41.ccls.	(\$1-alumna or alpha-alumna or (alpha near alumina)) with abrasive	"451.das"	20 "451" cles
288	3038	-	12	77604	2905	190	895	0	64929
S25	S26	227	828	S29	S30	531	23	S33	S34

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2005/01/21 16:01	2005/01/21:15:30	2005/01/21 15:30	2005/01/21 15:31	2005/01/21 16:01	2005/01/21:16:01	2005/01/24 09:38	2005/01/24-10:48
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US-PGPÜB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT US-PGPUB; US-PGPUB; EPO; JPO;	US-PGPUB; US-PGPUB; USOCR; EPO: JPO; US-PGPUB; US-PGPUB; US-PGPUB; US-PGPUB;	US-PGPUB: USDCR; EPO:JPO: DERWENT: US-PGPUB; USPAT; USPAT; USDCR; EPO: JPO; DERWENT
S32 and S34	(silica or (funed adj alumina)) with abrasive	(S32 or S36) and S34	S35 and (reducing adj.agent)	S37 and (reducing adj agent)	S36-and S34 S40 and (reducing adj agent)	T6454822".pn.	S43 and ((tridium adj.oxide.) or (tantalum same (oxidized.) oxide oxidizen!)) and ((polishing adj.pad or abrasive))
99	6947	1138	=	27	1109	64929	195
535	536	537	X38	839	S40	S43	42 82

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65:60	10:08	11:17	2005/01/24 10:15	2005/01/24 10:15	2005/01/24 10:15	2005/01/24 10:15	2005/01/24 10:16	2005/01/24 10:16	2005/01/24 10:17
2005/01/24 09:59	2005/01/24 10:08	2005/01/24 11:17	01/24	01/24	01/24	01/24	01/24	01/24	01/24
2005/	2005/	2005/	2005/	2002/	2005	2005	2005	2005,	2005
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US-PGPUB; USPAT	US-PGPUB USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCK; EPO; JPO; DERWENT	US-PGPUB USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB, USPAT; USOCR, EPO; JPO; DERWENT
(US-20020182982-\$ or US-20030013387-\$ or US-20040029495-\$ or US-20040132385-\$).did. or (US-6454822-\$ or US-6709316-\$).	9	(silicone adj oxide) with "Si"	ar4 meta	silicone near2 metal	ari metal	15	05	64	51
(US-2002C US-200300 US-200400 US-200400 (US-64548 did.	S45 and S46	(silicone a	silicone near4 mei	silicone ne	silicone near! metal	S43 and S51	S43 and S50	S43 and S49	S54 not S51
9	2	37	6851	2822	740	1	S	Ξ	10
S46	S4	S48	S49	850	158	852	SS	S54	255

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2005/01/24 10:23	2005/01/24.10:24	2005/01/24 10:47	2005/01/24 10:46	2005/01/24 10:49	2005/01/24 10:49	2005/01/24 10:50	2005/01/24 11:17	2005/01/24 11:17	2005/01/24 13:23
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OR	క	NO.	క	8	SO.	g.	OR	OR	S.
US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	us-pgpub; uspat; usocr; epo; jpo; derwent	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	US-PGPUB; USPAT; EPO; JPO; DERWENT
S54 not S53	S47 and (Indium adj oxide)	S43 and (iridium adj oxide)	.428° clas	(substrate or wafer or semiconductor or semi-conductor) with (iridium adj oxide)	543 and (tridium adj oxide)	((substrate or wafer or semiconductor or semi-conductor) with (indium adj oxide)) and ((polishing adj pad) or abrasive)	(copper adj oxide) with "Cut"	S63 and S43	(indium adj.oxde) and (polish polishing CVP ("chemical mechanical polishing"))
9	0	2	212721	609	2	15	1388	&	665
256	SS7	828	829	095	S61	295	S63	S64	S65

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3:23	3:24	3:24	60:	4:09	1.1
2005/01/24 13:23	2005/01/24 13:24	2005/01/24 13:24	2005/01/24 14:09	2005/01/24 14:09	2005/01/24 14:11
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22522	2282	2282	2282	S S 9 B	5565
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agen	Polisi Polisi	d (CMP 1 polishi	ne (CMI i polishi		
g adj agen) and (CMP inical polish) and (CMP inical polishi) same (CM inical polishi		
ucing adj agen	xide) and (CMP echanical polish	oxide) and (CMP echanical polishi	xide) same (CM echanical polishi	÷	e.
(reducing adj agen	adj oxide) and (CMP al mechanical polish	adj oxide) and (CMP al mechanical polishi	adj oxide) same (CM) al mechanical polishi	1".pn.	2° pn.
and (reducing adj agen	um adj.oxide).and (CMP emical mechanical polish	ium adj oxide) and (CMP emical mechanical polishi	ium adj oxide) same (CM) emical mechanical polishi	.7581".pn.	9572" pn.
S65 and (reducing adj agen	(irdium adi oxde) and (CMP ("chemical mechanical polishing"))	(indium adj oxide) and (CMP or ("chemical mechanical polishing"))	(indium adj oxde) same (CMP or ("chemical mechanical polishing"))	"4717581".pn.	"4679572" pn.
44 S65 and (reducing adj agent)			46. (Indium adj oxde) same (CM) ("chemical mechanical polishi	2 4717581".pn.	2 "4679572" pn.
44 S65 and (reducing adj agen	569 (tridium adj oxide) and (CMP ("chemical mechanical polish	569 (rindium adj oxide) and (CMP ("chemical mechanical polishi			